

HiPoSwitch – WP4

Device process development and technology transfer

- 100 m Ω normally-off generation 2 transistors with up to 600 V breakdown strength manufactured and shipped to partners
- Dynamic R_{ON} increase significantly reduced due to GaN:Fe-buffer
- Generation 2 test devices based on GaN:C-buffer, GaN:Fe-buffer and AlGaN-buffer distributed to partners for dynamic performance and reliability characterization
- Generation 3 devices with new 70 m Ω layout and reduced parasitic capacitances and new FP design have finished FE processing
- New source-connected FP design with step-SiN_x passivation gives no additional off-state leakage

Process modules for high volume manufacturing

- Contamination analysis on the Si-based technology tools and equipments has been performed
- Si-fab compatible Au-free ohmic contact module with 0.25 Ω mm contact resistance developed by IFAT
- Ohmic contact metal etching selective to the passivation layer (10:1) has been introduced
- Ion implantation for device isolation was optimized

Technology for quasi-vertical devices

- Process module for low-resistive interconnect between front-side contact and Si-substrate developed
- Bonding-over-active area without device degradation achieved

Benchmarking Si vs. SiC substrates

- Thermal resistance of GaN-layer plus substrate stack has been determined for SiC substrates and for Si substrates

Publications

- [1] J. Würfl, O. Hilt, E. Bahat-Treidel, R. Zhytnytska, K. Klein, P. Kotara, F. Brunner, A. Knauer, O. Krüger, M. Weyers, G. Tränkle, "Technological approaches towards high voltage, fast switching GaN power transistors", ECS Trans., vol. 52, no. 1, 979-989 (2013).
- [2] J. Würfl, O. Hilt, "Power Electronic Devices based on GaN: Advantages and Perspectives", Int. Conf. and Exhibition on Automotive Power Electronics, Paris, France, Apr. 3-4 (2013).
- [3] J. Würfl, O. Hilt, E. Bahat-Treidel, R. Zhytnytska, P. Kotara, O. Krüger, F. Brunner, M. Weyers, "Breakdown and Dynamic Effects in GaN Power Switching Devices", 40th International Symposium on Compound Semiconductors (ISCS), Kobe, Japan, May 19-23 (2013).
- [4] N. Badawi, O. Hilt, E. Bahat-Treidel, S. Dieckerhoff, H.-J. Würfl, "Switching Characteristics of 200V Normally-off GaN HEMTs", Int. Exhibition and Conf. for Power Electronics, Intelligent Motion, Renewable Energy and Energy Management (PCIM Europe), Nuremberg, Germany, May 14-16, ISBN 978-3-8007-3505-1, pp. 319-324 (2013).
- [5] P. Kotara, R. Zhytnytska, O. Hilt, E. Cho, F. Brunner, A. Thies, E. Bahat-Treidel, and J. Würfl, "Vertical Blocking Voltage Improvement of GaN HEMT Structures on n-SiC by Pre-Epitaxial Substrate Implantation", ECS Journal of Solid State Science and Technology, vol. 2, no. 8, N3064-N3067 (2013).
- [6] O. Hilt, P. Kotara, F. Brunner, A. Knauer, R. Zhytnytska, und J. Würfl, "Improved Vertical Isolation for Normally-off High Voltage GaN-HFETs on n-SiC Substrates", IEEE Transactions on Electron Devices, Vol. 60, Issue 10, pp. 3084-3090, 2013.
- [7] N. Badawi, O. Hilt, S. Dieckerhoff, E. Bahat-Treidel, R. Aguirre, J. Würfl, "Switching Performance of 400 V Normally-On and Normally-Off GaN HEMTs", 37th Workshop on Compound Semiconductor Devices and Integrated Circuits (WOCSDICE), Warnemünde, Germany, May 26-29, ISBN 978-3-00-041435-0, pp. 47-48 (2013).
- [8] J. Würfl, "Overview on Project 'GaN-Based Normally-Off High Power Switching Transistors for Efficient Power Converters' (HIPOSWITCH)", 37th Workshop on Compound Semiconductor Devices and Integrated Circuits (WOCSDICE), Warnemünde, Germany, May 26-29, ISBN 978-3-00-041435-0, p. 55 (2013).
- [9] E. Bahat-Treidel, O. Hilt, J. Würfl, "AlGaIn/GaN/AlGaIn/GaN:C on N-SiC Power HEMT with Low Switching Dynamic RON and High Breakdown Voltage", 37th Workshop on Compound Semiconductor Devices and Integrated Circuits (WOCSDICE), Warnemünde, Germany, May 26-29, ISBN 978-3-00-041435-0, pp. 61-62 (2013).
- [10] R. Zhytnytska, O. Hilt, J. Würfl and G. Tränkle, "Influence of device periphery design on breakdown and ON-state resistance of AlGaIn/GaN HEMTs", Proceedings of 37th of Workshop on Compound Semiconductor Devices and Integrated Circuits (WOCSDICE 2013), 2013, p.65.